

Sub (33) (Cont'd.)
in an opening having an aspect ratio of at least 2.0; and

ii) depositing a second amount of said metal on said first amount of metal.

SUPPORT FOR THE AMENDMENT

Support for the amendment to claim 1 is found on page 4, lines 21-22; page 6, line 12 of the specification and in claim 4 as originally presented. Support for claim 22 is found in claims 1 and 9 as originally presented and on page 4, lines 21-22 of the specification. Support for claim 23 is found on page 6, line 12 of the specification and claim 4 as originally presented. Support for claim 24 is found in claims 1, 4 and 9 as originally presented and on page 6, line 12 of the specification. No new matter would be added to this application by entry of this amendment.

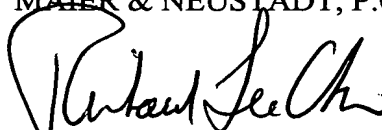
Upon entry of this amendment claims 1-24 will now be active in this application.

The present application is a continuation application of U.S. Serial No. 08/970,107 filed on November 13, 1997, now allowed and is directed to a method of forming a layer of metal in which a second amount of metal is deposited on a seed layer under conditions sufficient to inhibit formation of filamentous metal phases having a resistivity greater than that of said metal as well as methods of forming a layer of aluminum-containing metal.

Applicants submit that this application is now in conditions for examination on the merits
and early notification of such action is earnestly solicited.

Respectfully submitted,

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